

L Number	Hits	Search Text	DB	Time stamp
1	2	("6723632").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 07:40
44	6677	((critical near3 dimension) or (line near3 width) or (distance near5 line)) with range	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 09:24
45	9474	((photoresist adj mask) or (photo adj mask) or mask or reticle) and (parasitic near4 capacitance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 11:27
46	64	((critical near3 dimension) or (line near3 width) or (distance near5 line)) with range) and ((photoresist adj mask) or (photo adj mask) or mask or reticle) and (parasitic near4 capacitance))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 08:16
47	7833	716/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 08:17
48	1	((critical near3 dimension) or (line near3 width) or (distance near5 line)) with range) and ((photoresist adj mask) or (photo adj mask) or mask or reticle) and (parasitic near4 capacitance))) and 716/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 09:20
49	22	penetration and 716/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 09:21
50	14	((critical near3 dimension) or (line near3 width) or (distance near5 line)) and (penetration and 716/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 09:34
51	6	((photoresist adj mask) or (photo adj mask) or mask or reticle) and ((critical near3 dimension) or (line near3 width) or (distance near5 line)) and (penetration and 716/\$.ccls.))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 09:33
52	0	((photoresist adj mask) or (photo adj mask) or mask or reticle) and ((critical near3 dimension) or (line near3 width) or (distance near5 line)) and (penetration and 716/\$.ccls.))) and (parasitic near4 capacitance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 09:31
53	2507	penetrat\$3 and (parasitic near4 capacitance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 10:09
54	1737	((photoresist adj mask) or (photo adj mask) or photolithograph\$5 or mask or reticle) and (penetrat\$3 and (parasitic near4 capacitance))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 10:20
55	432	((critical near3 dimension) or (line near3 width) or (distance near5 line)) and ((photoresist adj mask) or (photo adj mask) or photolithograph\$5 or mask or reticle) and (penetrat\$3 and (parasitic near4 capacitance)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 11:29
56	1	((critical near3 dimension) or (line near3 width) or (distance near5 line)) and ((photoresist adj mask) or (photo adj mask) or photolithograph\$5 or mask or reticle) and (penetrat\$3 and (parasitic near4 capacitance))) and 716/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 09:36
59	4	((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3) same (inter adj line)) and (parasitic near4 capacitance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 10:13

60	28	(penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3) and (inter adj line) and (parasitic near4 capacitance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 11:25
61	21	((critical near4 dimension) or (line near4 width) or (distance near5 line) or (line near4 dimension)) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3) and (inter adj line) and (parasitic near4 capacitance))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 10:15
62	0	716/\$.ccls. and (((critical near4 dimension) or (line near4 width) or (distance near5 line) or (line near4 dimension)) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3) and (inter adj line) and (parasitic near4 capacitance)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 10:16
63	20	(simulat\$3 or design\$3 or model\$4) and (((critical near4 dimension) or (line near4 width) or (distance near5 line) or (line near4 dimension)) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3) and (inter adj line) and (parasitic near4 capacitance)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 12:56
64	6	simulat\$3 and (((critical near4 dimension) or (line near4 width) or (distance near5 line) or (line near4 dimension)) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3) and (inter adj line) and (parasitic near4 capacitance)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 10:17
65	12	((photoresist adj mask) or (photo adj mask) or photolithograph\$5 or mask or reticle) and ((simulat\$3 or design\$3 or model\$4) and (((critical near4 dimension) or (line near4 width) or (distance near5 line) or (line near4 dimension)) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3) and (inter adj line) and (parasitic near4 capacitance))))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 10:20
66	12107	(penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3 or shield\$3) and (parasitic near4 capacitance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 13:10
67	5362	((photoresist adj mask) or (photo adj mask) or mask or reticle or photolithograph\$5) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3 or shield\$3) and (parasitic near4 capacitance))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 11:29
68	76	((photoresist adj mask) or (photo adj mask) or mask or reticle or photolithograph\$5) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3 or shield\$3) and (parasitic near4 capacitance))) and 716/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 11:29
69	14	((critical near3 dimension) or (line near3 width) or (distance near5 line)) and (((photoresist adj mask) or (photo adj mask) or mask or reticle or photolithograph\$5) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3 or shield\$3) and (parasitic near4 capacitance))) and 716/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 12:55
70	13	"5136358"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 12:54

71	3	((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3 or shield\$3) and (parasitic near4 capacitance)) and "5136358"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 12:55
72	2	((critical near3 dimension) or (line near3 width) or (distance near5 line)) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3 or shield\$3) and (parasitic near4 capacitance)) and "5136358")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 13:09
73	2	(simulat\$3 or design\$3 or model\$4) and (((critical near3 dimension) or (line near3 width) or (distance near5 line)) and ((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3 or shield\$3) and (parasitic near4 capacitance)) and "5136358"))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 13:06
74	24	((("5808366") or ("5796986") or ("5761080") or ("5694344") or ("5610833") or ("5500804") or ("5410491") or ("5379231") or ("5236871") or ("4884122") or ("3838442"))).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 13:06
75	7	716/\$.ccls. and (((("5808366") or ("5796986") or ("5761080") or ("5694344") or ("5610833") or ("5500804") or ("5410491") or ("5379231") or ("5236871") or ("4884122") or ("3838442"))).PN.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 13:06
76	3	((critical near3 dimension) or (line near3 width) or (distance near5 line)) and (716/\$.ccls. and (((("5808366") or ("5796986") or ("5761080") or ("5694344") or ("5610833") or ("5500804") or ("5410491") or ("5379231") or ("5236871") or ("4884122") or ("3838442"))).PN.))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 13:09
77	0	((penetrat\$3 or insert\$3 or interven\$3 or mediat\$3 or interpos\$3 or shield\$3) and (parasitic near4 capacitance)) and (((critical near3 dimension) or (line near3 width) or (distance near5 line)) and (716/\$.ccls. and (((("5808366") or ("5796986") or ("5761080") or ("5694344") or ("5610833") or ("5500804") or ("5410491") or ("5379231") or ("5236871") or ("4884122") or ("3838442"))).PN.)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 13:10
78	2	(((critical near3 dimension) or (line near3 width) or (distance near5 line)) and (716/\$.ccls. and (((("5808366") or ("5796986") or ("5761080") or ("5694344") or ("5610833") or ("5500804") or ("5410491") or ("5379231") or ("5236871") or ("4884122") or ("3838442"))).PN.))) and (parasitic near4 capacitance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 13:10
-	9463	((photoresist adj mask) or (photo adj mask) or mask or reticle) and (parasitic near4 capacitance)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 08:15
-	13	((critical near3 dimension) with range) and (((photoresist adj mask) or (photo adj mask) or mask or reticle) and (parasitic near4 capacitance))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/14 08:12
-	2	("6414367").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/10/13 16:17